

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	1	"6017810".PN.	USPAT; USOCR	OR	OFF	2005/04/07 10:15
L4	1172	(resist or photoresist) same pattern\$4 same ("hard mask" or SOG or "spin on glass") same (trenches or openings)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:19
L5	894	(resist or photoresist) same pattern\$4 same "hard mask" same (trenches or openings) same etch\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:19
L6	846	5 and semiconductor	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:22
L7	204	(resist or photoresist) same (pattern\$4 or mask\$4) same (SOG or "spin on glass") same (trenches or openings) same etch\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:23
L8	3071	(resist or photoresist) and pattern\$4 and (SOG or "spin on glass" or BPSG) same (trenches or openings or vias) and etch\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:21
L9	1927	(resist or photoresist) and pattern\$4 and (SOG or "spin on glass" or BPSG) same (trenches or openings or vias) and etch\$4 and (CMP or planariz\$4)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:21
L10	1872	9 and semiconductor	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:27
L11	1463	(resist or photoresist) same (pattern\$4 or mask\$4) same (SOG or "spin on glass" or "hard mask") same (trenches or openings) same (etch\$4 or remov\$4)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:24
L12	8	goodner-michael-d.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:25
L13	0	leet-bob-e.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:26
L14	6	meagley-robert-p.in.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/07 10:26